INVENTOR INFORMATION

Inventor One Given Name::

Family Name::

Mailing Address Line One::

Mailing Address Line Two::

City::

Country::

City of Residence::
Country of Residence::

Citizenship Country::

Inventor Two Given Name::

Family Name::

Mailing Address Line One::

Mailing Address Line Two::

City::

Country::

City of Residence::

Country of Residence:: Citizenship Country::

Inventor Three Given Name::

Family Name::

Mailing Address Line One::

Mailing Address Line Two::

City::

Country::

City of Residence::

Country of Residence::

Citizenship Country::

CORRESPONDENCE INFORMATION

Correspondence Customer Number::

APPLICATION INFORMATION

Title Line One::
Title Line Two::

Application Type::

Docket Number::

REPRESENTATIVE INFORMATION

Representative Customer Number::

PRIOR FOREIGN APPLICATIONS

Foreign Application One::

Filing Date::

Country::

Priority Claimed::

Jun

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23599

POLYMER, CHEMICALLY AMPLIFIED RESIST

COMPOSITION AND PATTERNING PROCESS

UTILITY KOJIM-393

23599

2000-127513

4/27/2000 Japan

YES

ASSIGNEE INFORMATION

Name of Assignee:: Address Line One:: City:: State or Province:: Country::

Shin-Etsu Chemical Co., Ltd. 6-1, Otemachi, 2-chome Chiyoda-ku, Tokyo Tokyo Japan